Supporting Information

Single-Atom Underpotential Deposition at Specific Sites of N-Doped Graphene for Hydrogen Evolution Reaction Electrocatalysis

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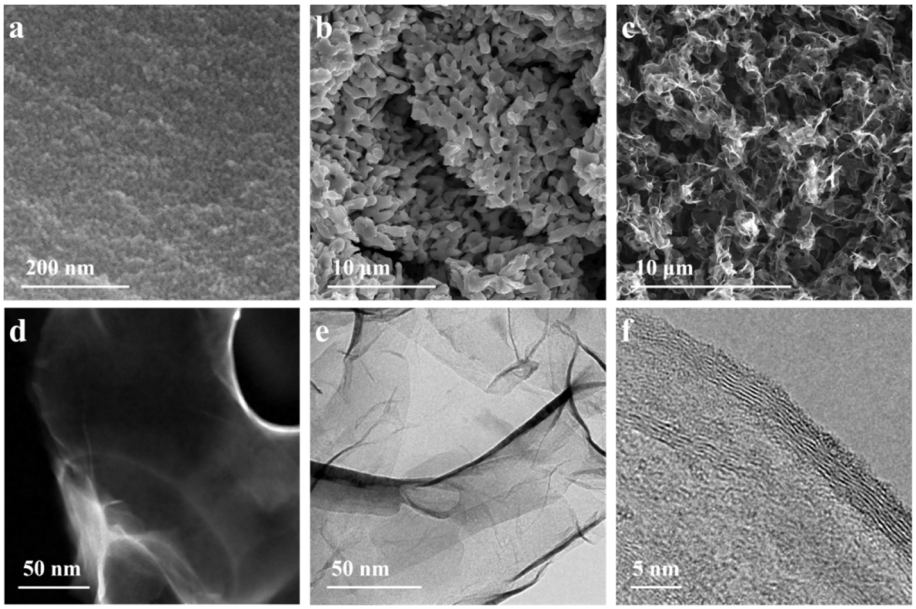


Figure S1. SEM images of np-Ni template (a) before and (b) after growing graphene, (c) np-NG after etching Ni template. (d) STEM and (e) TEM images of np-NG. (f) HRTEM image of the cross-section of np-NG.

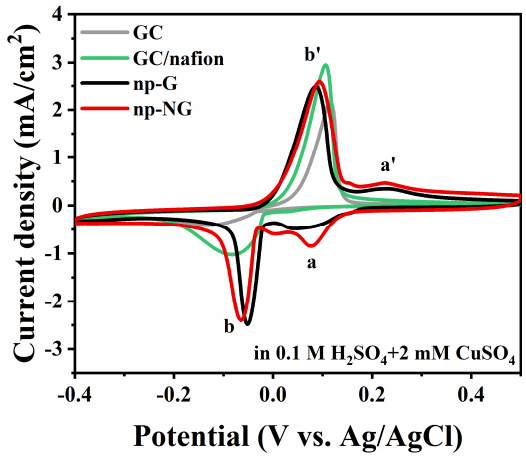


Figure S2. CV curves of different samples in 0.5 M H_2SO_4 containing 2 mM $CuSO_4$.

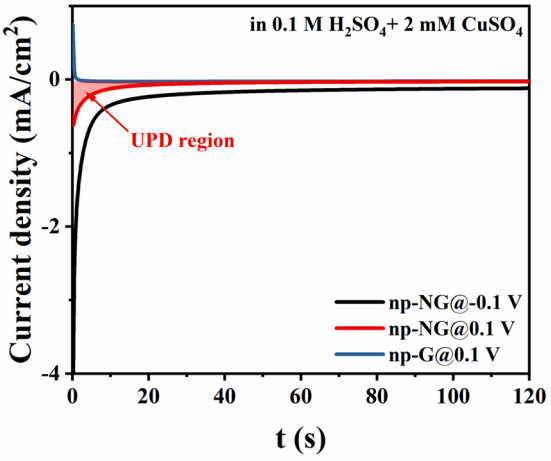


Figure S3. Chronoamperometry curves of the deposition of Cu at different potentials.

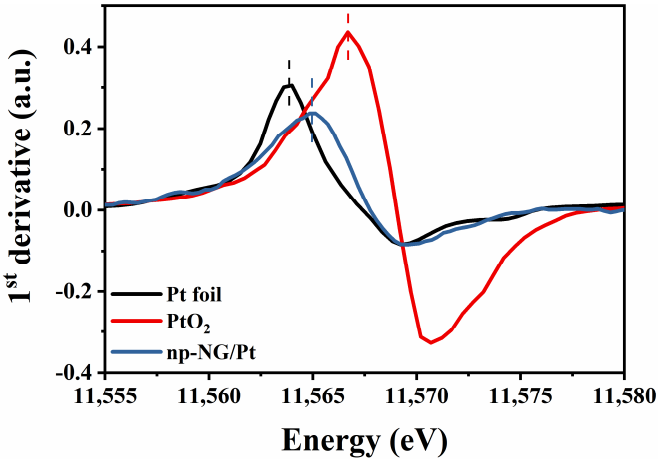


Figure S4. The corresponding first-derivative XANES spectra of different Pt samples.

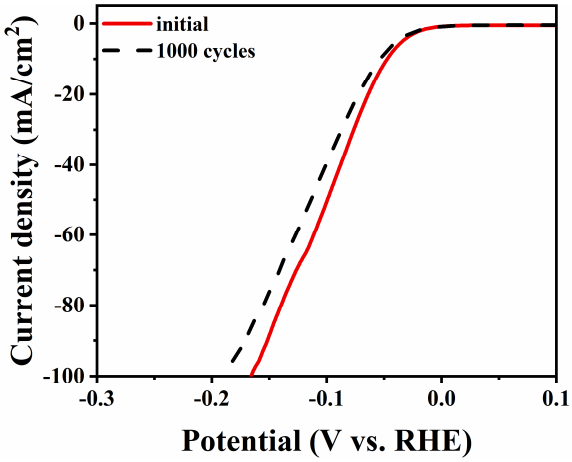


Figure S5. Stability test of np-NG/Pt by potential cycling before and after 1000 cycles.